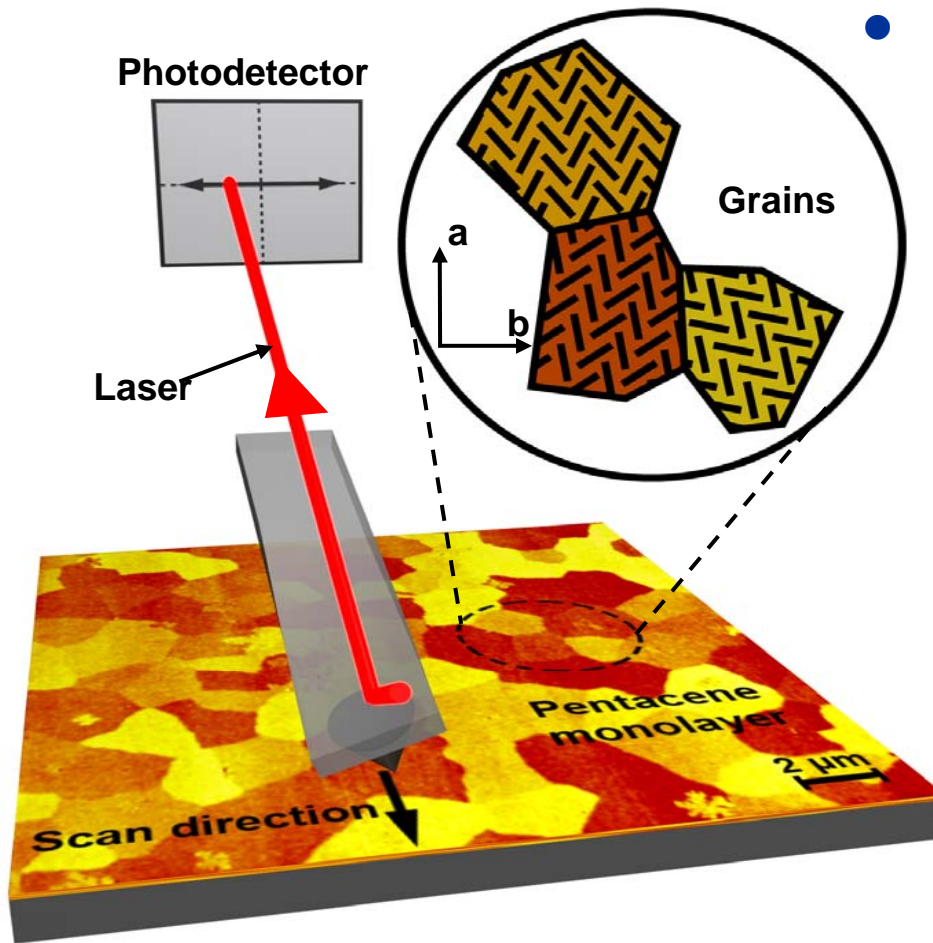


# Transverse Shear Microscopy

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NNIN Facility utilized: Characterization Facility



- Transverse Shear Microscopy (TSM)
  - ◆ A contact mode variant of Atomic Force Microscopy
  - ◆ Reveal grains in ultrathin polycrystalline organic semiconductor films
  - ◆ Sensitive to relative orientation between the scan direction and the crystallographic direction
  - ◆ Can be used to generate Grain Orientation Maps
- TSM can be used for following analysis:
  - ◆ Grain Shape
  - ◆ Grain Size
  - ◆ Grain Boundary
  - ◆ Diffusion Activation Energy